

USER GUIDE : PNE (NX-1) CONVENTIONAL NEGATIVE PLATE

PLATE TYPE	EXPOSURE TECHNICAL DATA					PROCESSING TECHNICAL DATA				REFERENCE		
	EXPOSURE IN UNITS	EXPOSURE IN MJ/CM2	LAMP TYPE	LAMP WATTAGE	LAMP DISTANCE	DEVELOPER USED	MIXING RATIO	DEVELOPING TIME	DEVELOPING TEMP	UGRA STEP WEDGE		
										STEPS	LINE (+) & (-)	DOT
NEGATIVE WORKING	90 UNITS	90 - 120 MJ/CM2	UV LAMP	4000 W	0.9 M	PNE, XDS-93 KODAK 956 (ready-to-use) KODAK 960 (concentrated) FUJI DN-3C (ready-to-use)	1 : 5 1 : 1 1 : 10 1 : 1	25 - 35 SEC	20 - 25° C	3 STEPS SOLID	10 um (-) 4 um (+)	2% - 98%

ADDITIONAL INSTRUCTIONS & INFORMATIONS

(1)
STRONG CHEMICALS & AGGRESSIVE BRUSHING ON THE PLATES (INSIDE THE PROCESSOR) IS HARMFUL TO PNE NEGATIVE PLATES. IF STEP WEDGE READING IS UNATTAINABLE BASED ON THIS RECOMMENDED OPERATING INSTRUCTIONS, PLEASE ADJUST BRUSHES PRESSURE ON THE PLATE DURING DEVELOPMENT TO ATTAIN BEST RESULTS.

(2)
PNE NX-1 CAN BE PROCESSED USING AN AUTOMATIC POSITIVE PROCESSOR. IF THE POSITIVE PROCESSOR COMES WITH BRUSHES, ADJUSTMENT OF THE BRUSHING PRESSURE ON THE PLATES (IN THE PROCESSOR) DURING DEVELOPMENT MAY BE NECESSARY TO OBTAIN BEST RESULTS.

OPERATING EQUIPMENT	MODEL / NAME	COUNTRY OF ORIGIN
EXPOSURE MACHINE	MONTAKOP RAPID 95	GERMANY
NEGATIVE PLATE PROCESSOR	INTER PLATER 88	USA

BAKING CONDITIONS	
TEMPERATURE	APPROX. TIME
250 - 280° C	2 MINS

**** All information above are provided as general operating guide. Adjustments based on users' operating conditions are required to achieve the desired results. ****